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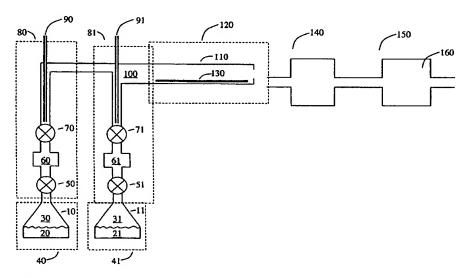
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before the expiration of the time limit for amending the claims and to be republished in the event of receipt of

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For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.

(54) Title: VAPOR DEPOSITION OF OXIDES, SILICATES AND PHOSPHATES



(57) Abstract: Metal silicates or phosphates are deposited on a heated substrate by the reaction of vapors of alkoxysilanols or alkylphosphates along with reactive metal amides, alkyls or alkoxides. For example, vapors of tris-(ter-butoxy)silanol react with vapors of tetrakis(ethylmethylamido)hafnium to deposit hafnium silicate on surfaces heated to 300 °C. The product film has a very uniform stoichiometry throughout the reactor. Similarly, vapors of diisopropylphosphate react with vapors of lithium bis(ethyldimethylsilyl)amide to deposit lithium phosphate films on substrates heated to 250 °C. supplying the vapors in alternating pulse produces these same compositions with a very uniform distribution of thickness and excellent step coverage.



International Application No PCT/US 01/30507

A. CLASSI IPC 7	FICATION OF SUBJECT MATTER C23C16/40 C23C16/44		*								
According to	According to International Patent Classification (IPC) or to both national classification and IPC										
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Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched											
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C. DOCUME	ENTS CONSIDERED TO BE RELEVANT										
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	er documents are listed in the continuation of box C.	X Patent family mem	bers are listed in annex.								
		"T" later document published or priority date and not	d after the international filing date in conflict with the application but								
conside	nt defining the general state of the art which is not ered to be of particular relevance		principle or theory underlying the								
filing da	ata	cannot be considered n	elevance; the claimed invention novel or cannot be considered to								
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2.15		PC1/US 01/3050/		
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International application No. PCT/US 01/30507

Box I Observations where certain claims were found unsearchable (C ntinuation 1 item 1 of first sheet)
This International Search Report has not been established in respect of certain claims under Article 17(2)(a) for the following reasons:
1. Claims Nos.: because they relate to subject matter not required to be searched by this Authority, namely:
Claims Nos.: because they relate to parts of the International Application that do not comply with the prescribed requirements to such an extent that no meaningful International Search can be carried out, specifically:
Claims Nos.: because they are dependent claims and are not drafted in accordance with the second and third sentences of Rule 6.4(a).
B x II Observations where unity of invention is lacking (Continuation of item 2 of first sheet)
This International Searching Authority found multiple Inventions in this International application, as follows:
see additional sheet
As all required additional search fees were timely paid by the applicant, this International Search Report covers all searchable claims.
2. As all searchable claims could be searched without effort justifying an additional fee, this Authority did not invite payment of any additional fee.
3. As only some of the required additional search fees were timely paid by the applicant, this International Search Report covers only those claims for which fees were paid, specifically claims Nos.: 1-11,22-24,28-30
4. No required additional search fees were timely paid by the applicant. Consequently, this International Search Report is restricted to the Invention first mentioned in the claims; it is covered by claims Nos.:
Remark on Protest The additional search fees were accompanied by the applicant's protest. X No protest accompanied the payment of additional search fees.

FURTHER INFORMATION CONTINUED FROM PCT/ISA/ 210

This International Searching Authority found multiple (groups of) inventions in this international application, as follows:

1. Claims: 1-11,22-24

CVD process using alkoxysilan(di)ol.

2. Claims: 12-21,25

CVD process using bis(alkyl)phosphates.

3. Claims: 26,27,31,32

CVD process using arene hydrates.

4. Claims: 28-30

CVD process using amides and alcohol or water.

Information on patent family members

Interior nal Application No
PCT/US 01/30507

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